

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION
METHOD OF PHOTOMASK, AND
FABRICATION METHOD OF
SEMICONDUCTOR INTEGRATED
CIRCUIT



) Group Art Unit: 1756
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Examiner: S. Mohamedulla
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AMENDMENT UNDER 37 C.F.R. §1.111

Assistant Commissioner for Patents
Washington, D.C. 20231

Date: October 18, 2001

Sir:

This amendment responds to the Office Action dated June 19, 2001 (Paper No. 12).

Concurrently filed with this amendment is a Petition for Extension of Time for one month and an attached explanation of a difference between different types of films. Please amend the above-noted application as follows:

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OCT 23 2001

TC 1700

10/19/2001 NROCHA1 00000097 09320946

01 FC:102 168.00 DP

IN THE CLAIMS:

Please replace claims 5, 7, 13, 15 and 22 as follows:

SUPP D2

5. (Twice Amended) A photomask comprising:
a transparent substrate;
a hollow section formed on a surface of said transparent substrate;
a shade pattern made up of a shade film, said shade film formed in said hollow section; and